



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/050,373
Filing Date January 15, 2002
Inventor Gurtej S. Sandhu et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Laura M. Schillinger
Attorney's Docket No. MI22-1896
Title: Methods of Forming a Nitrogen Enriched Region

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References - See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated:

December 26, 2002

By:

Jennifer J. Taylor
Jennifer J. Taylor, Ph.D.
Reg. No. 48,711

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LIST OF ART CITED BY APPLICANT
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Gurtej S. Sandhu et al.FILING DATE
January 15, 2002GROUP
2813

U S PATENT DOCUMENTS

*Examiner's Initial	TRADEMARK	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,837,598	11/17/98	Aronowitz et al.			
	AB	US 6,450,116 B1	09/17/02	Noble et al.			
	AC	4,605,447	08/12/86	Brotherton et al.			
	AD	US 6,207,586 B1	03/27/01	Ma et al.			
	AE	5,837,592	11/17/98	Chang et al.			
	AF	5,334,554	08/02/94	Lin et al.			
	AG	US 6,297,162 B1	10/02/01	Jang et al.			
	AH	US 6,436,771 B1	08/20/02	Jang et al.			
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR		
	AS		
	AT		

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP §69. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.